editors ought to be changed regularly." During his tenure, publication of the bimonthly journal switched to the American Institute of Physics and the number of pages roughly doubled. "Metzner did an outstanding job of achieving the highest quality combined with rapid publication, and I hope to maintain it as the preeminent journal of rheology," Denn said.

Denn earned a PhD in chemical engineering from the University of Minnesota in 1964. He was on the chemical engineering faculty of the University of Delaware from 1965 to 1981, and he then joined the University of California, Berkeley, as a professor of chemical engineering. Since 1983 he has also been program leader for polymers at Lawrence Berkeley National Laboratory's Center for Advanced Materials in the lab's materials sciences division. His research in polymer rheology and processing has focused on anisotropic polymers, flow instabilities, polymer-surface interactions and process modeling. From 1985 to 1991 Denn served as editor of the American Institute of Chemical Engineers' AIChE Journal.

AVS Elects McGuire to be President Elect

n 1 January Gary E. McGuire will become president elect of the American Vacuum Society. He was elected to that position this fall to succeed William D. Sproul, who will become the society's president in 1996.

McGuire, who holds a PhD in inorganic chemistry from the University of Tennessee, is director of electronic materials and devices at the Microelectronics Center of North Carolina, in Research Triangle Park, North Carolina. Prior to joining MCNC in 1987, he spent ten years at Tektronix in Beaverton, Oregon, and five years at Texas Instruments in Dallas. His research includes surface analysis techniques, thin-film deposition techniques and novel semiconductor materials and devices. McGuire serves as editor of the Journal of Vacuum Science and Technology B.

Other results of the AVS election were as follows: William D. Westwood of Northern Electric R&D Laboratory was reelected clerk and N. Rey Whetten, the AVS technical director, was reelected treasurer. Ellen B. Stechel of Sandia National Laboratories and Jerry M. Woodall of Purdue University were chosen as AVS directors. Eric M. Stuve of the University of Washington and John M. White of the University of Texas at Austin were elected trustees.

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